

Fig. 1

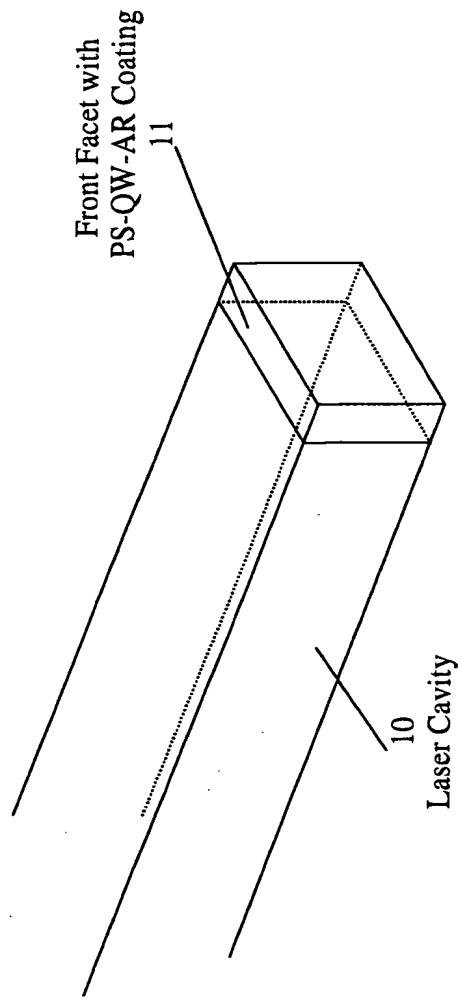


Fig. 2

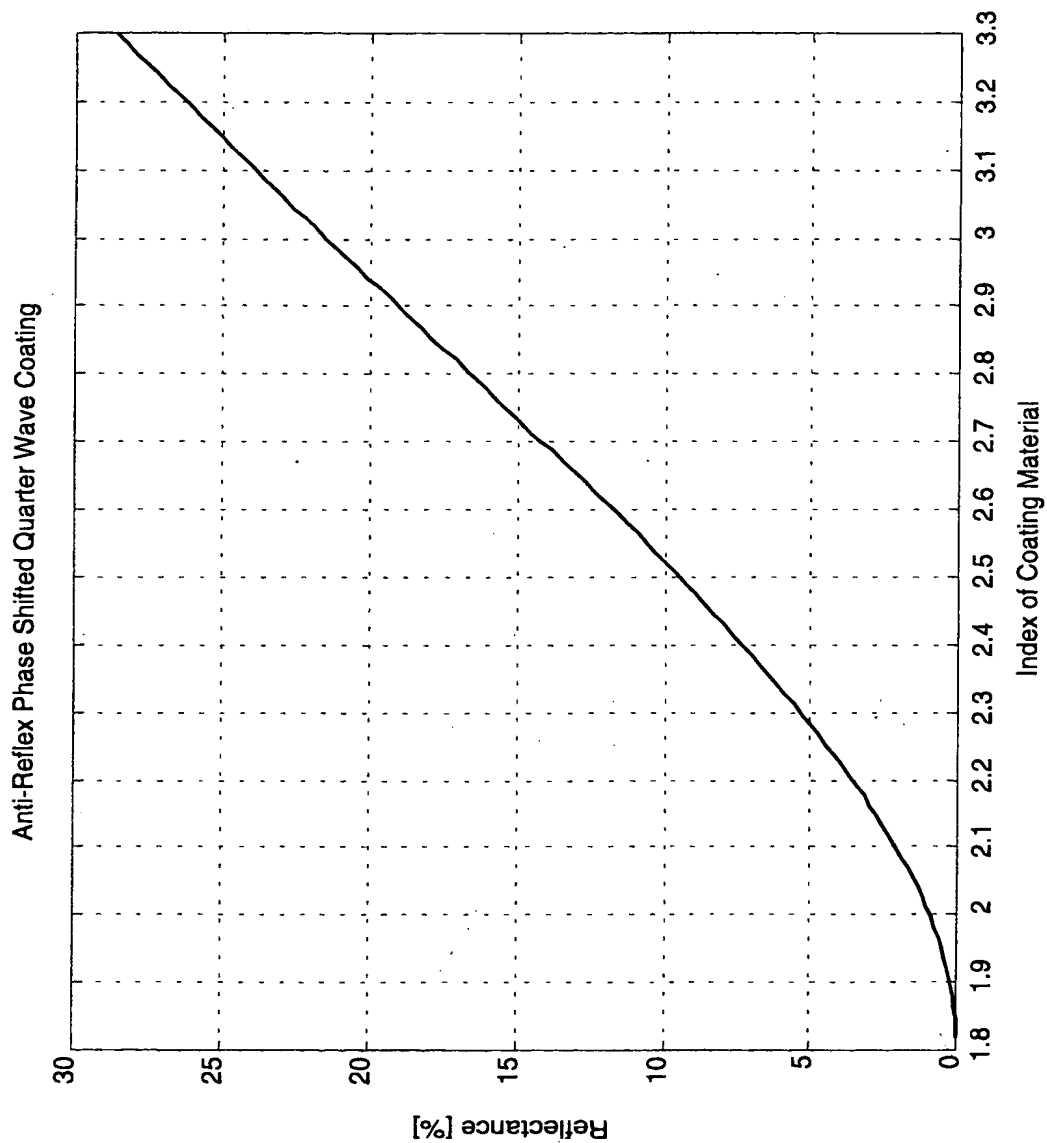
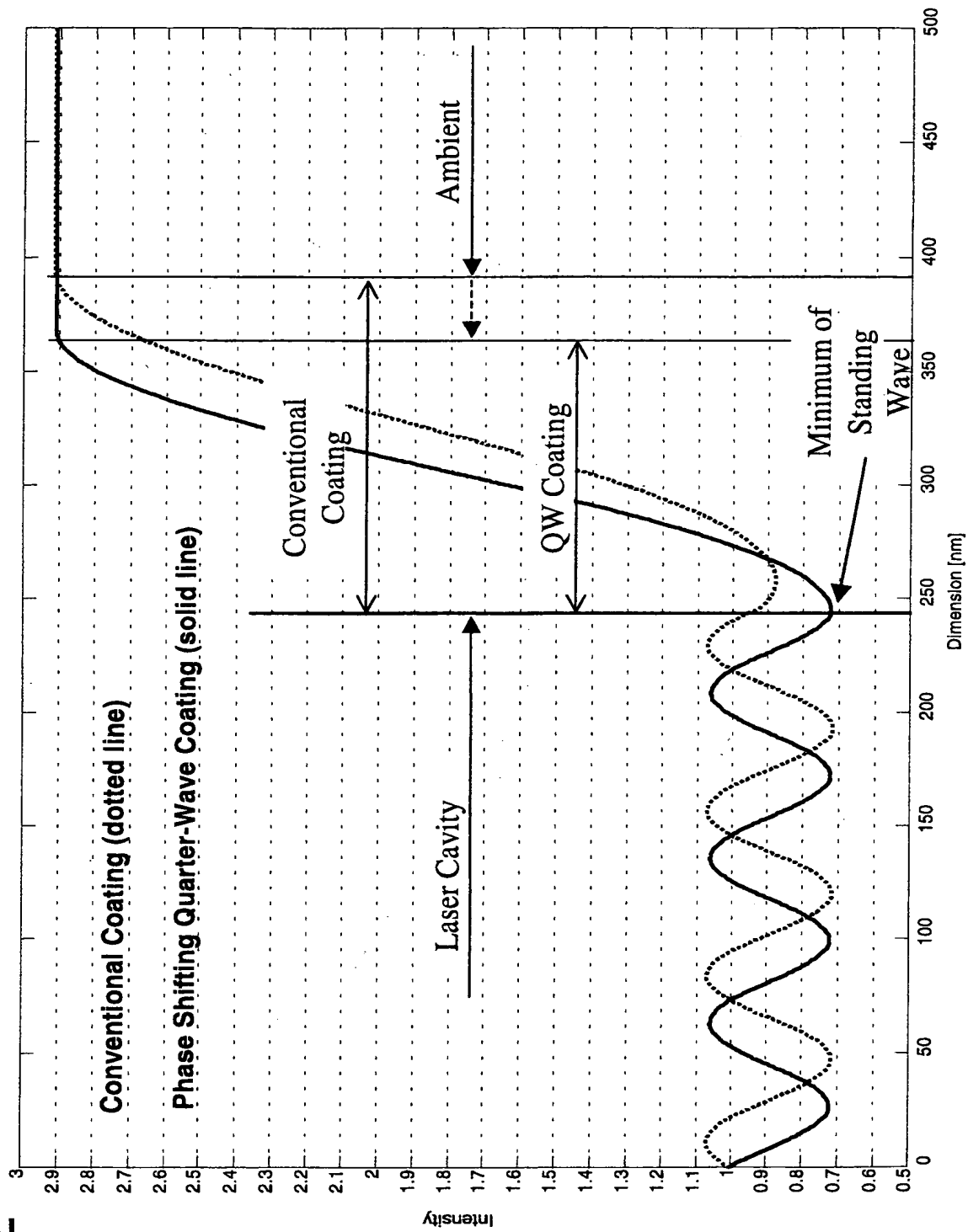
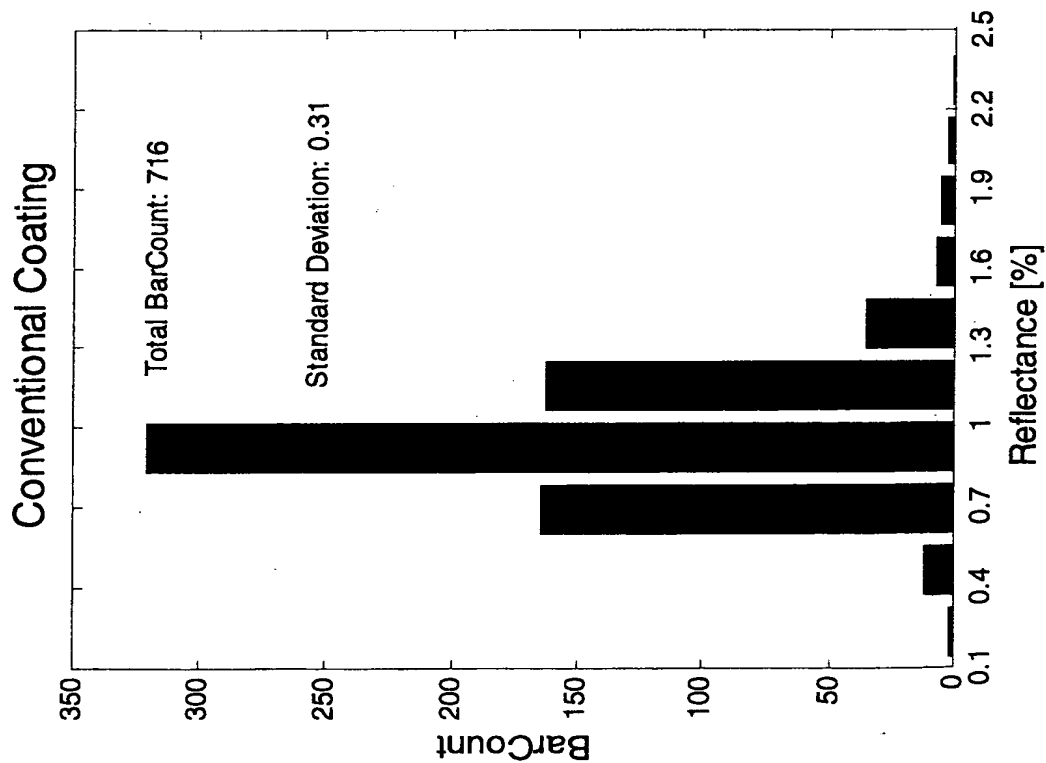


Fig. 3



*Fig. 4(a)*



*Fig. 4(b)*

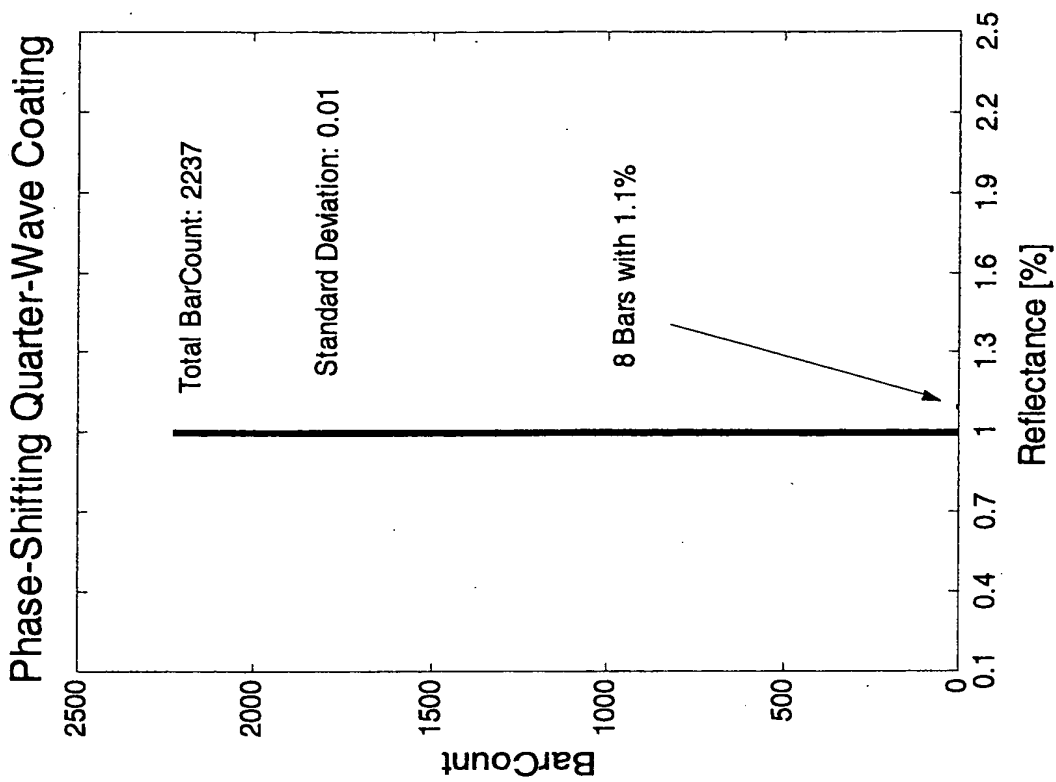
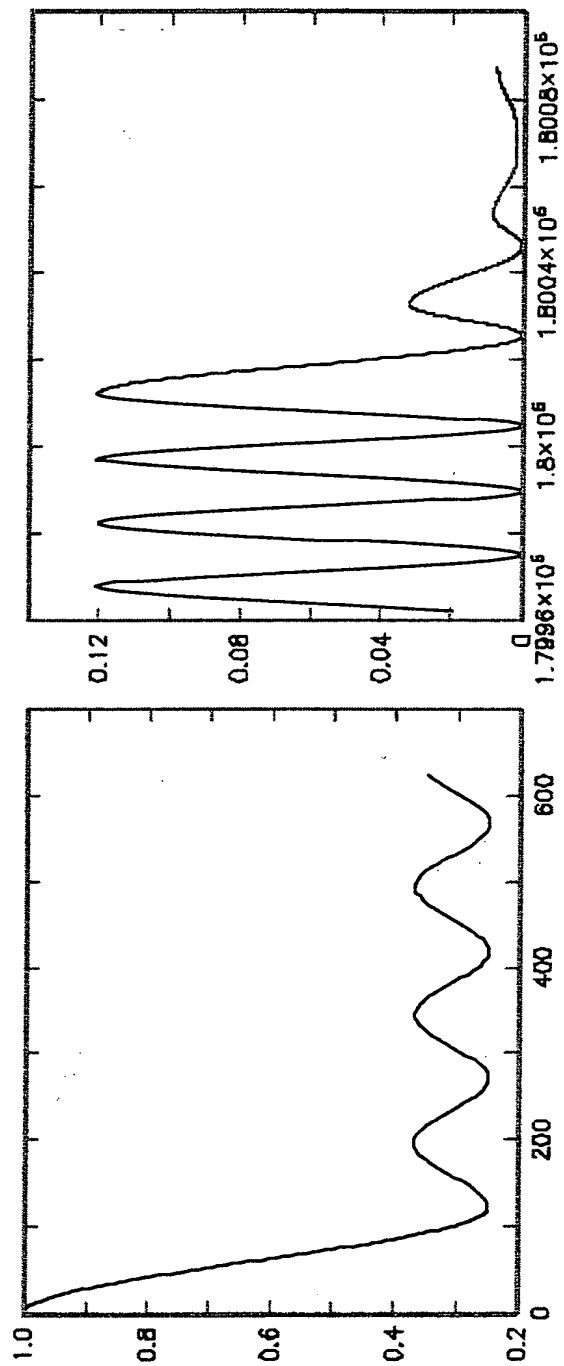
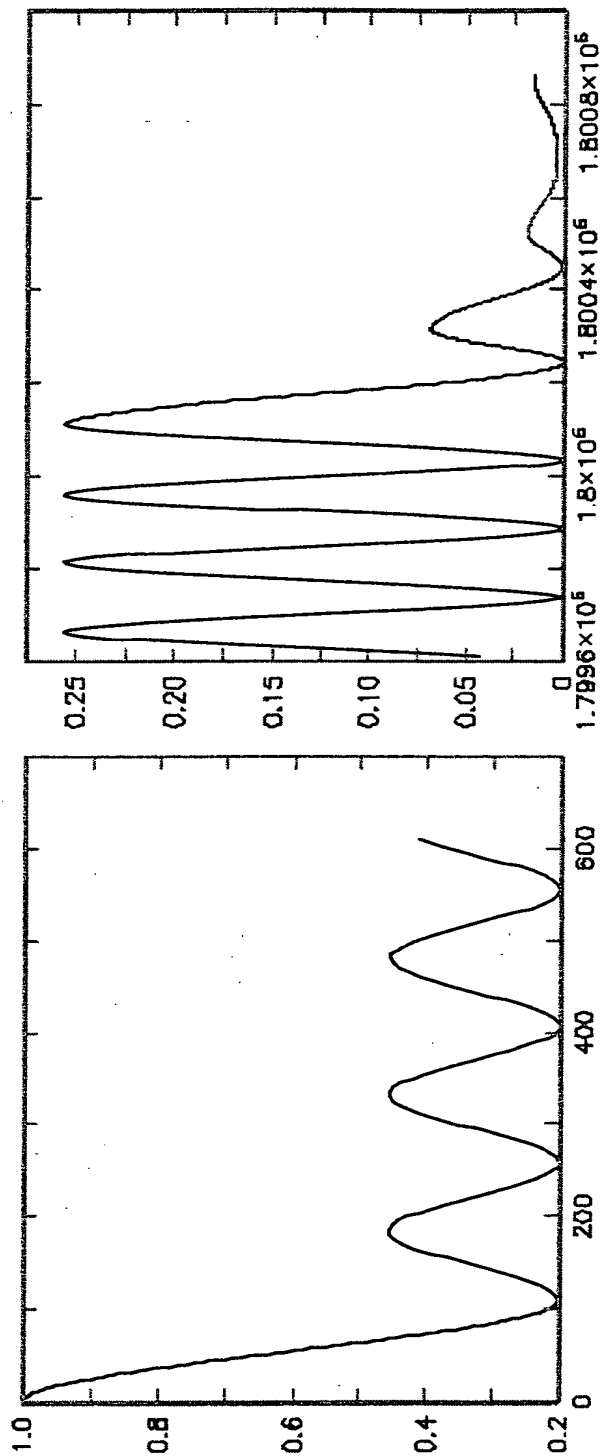


Fig. 5



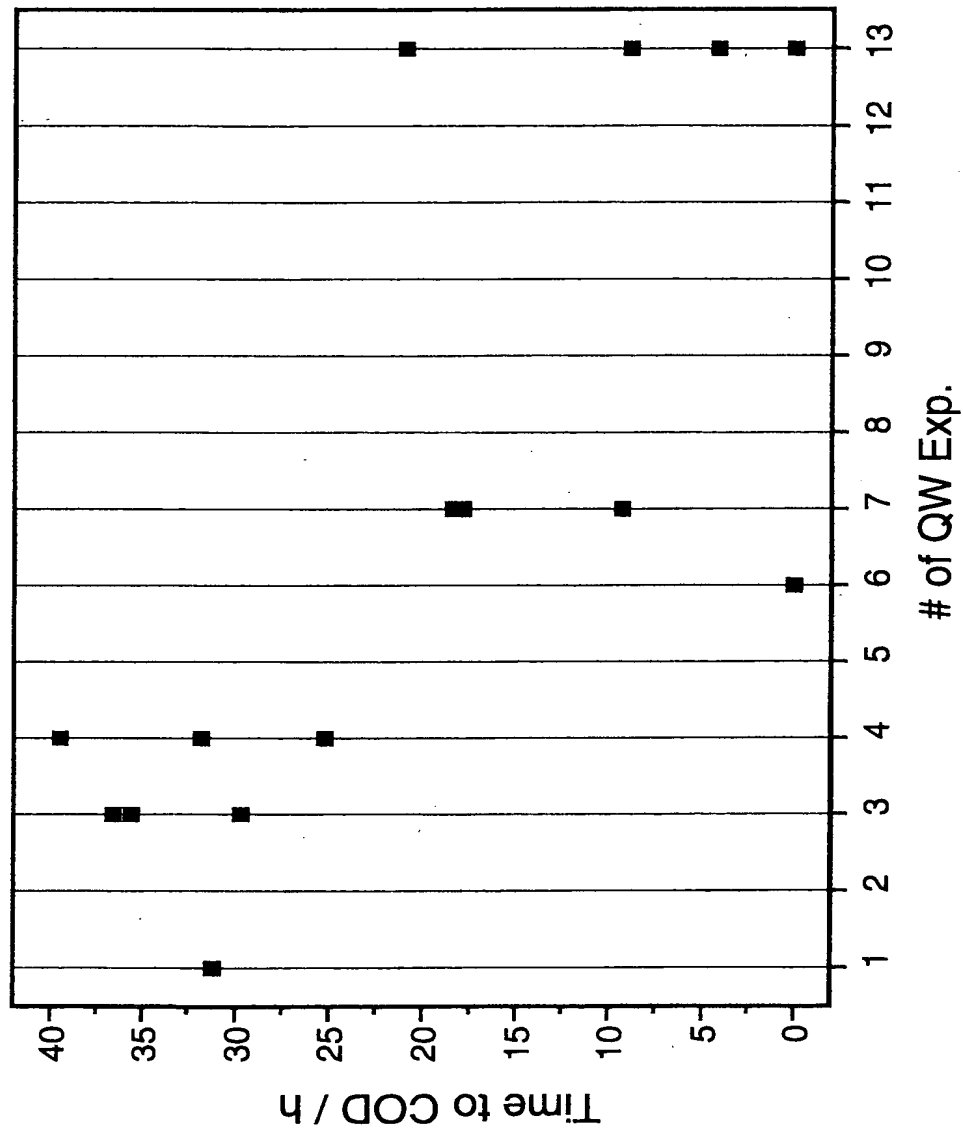
Phase Shifting Quarter Wave Coating with a 1 % Reflectance

Fig. 6



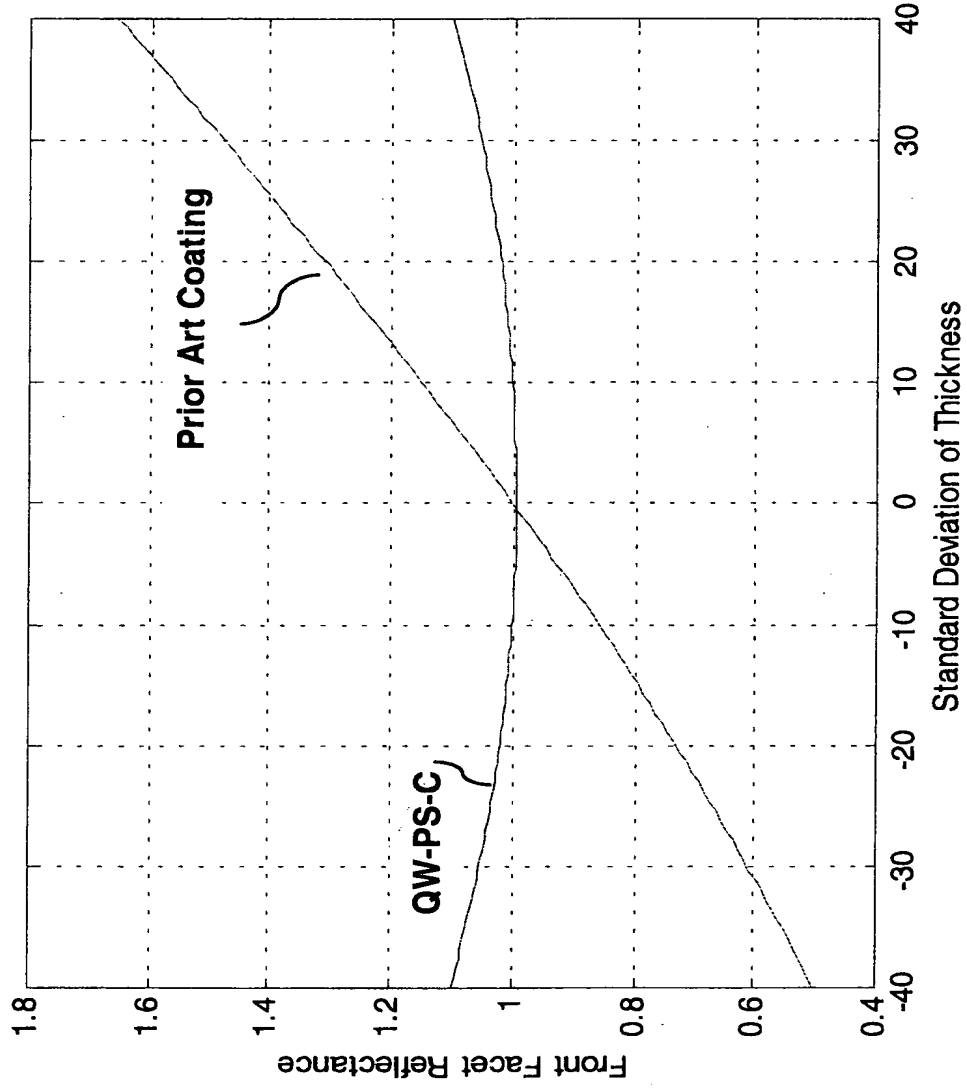
Phase Shifting Quarter Wave Coating with a 4 % Reflectance

Fig. 7



Time to COD vs. # of QW Exp

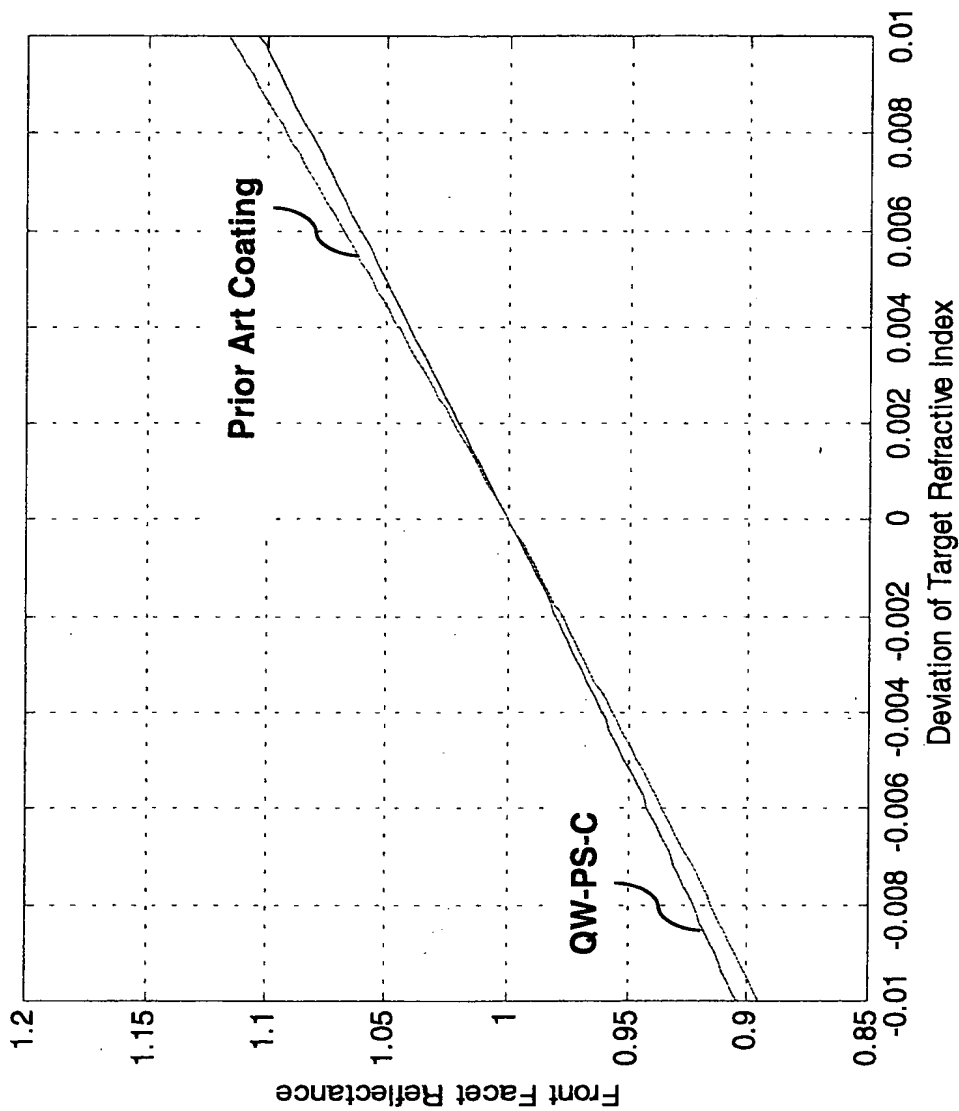
Fig. 8



Dependence of reflectance on thickness variation



Fig. 9



Dependence of Reflectance on index variation

Fig. 10

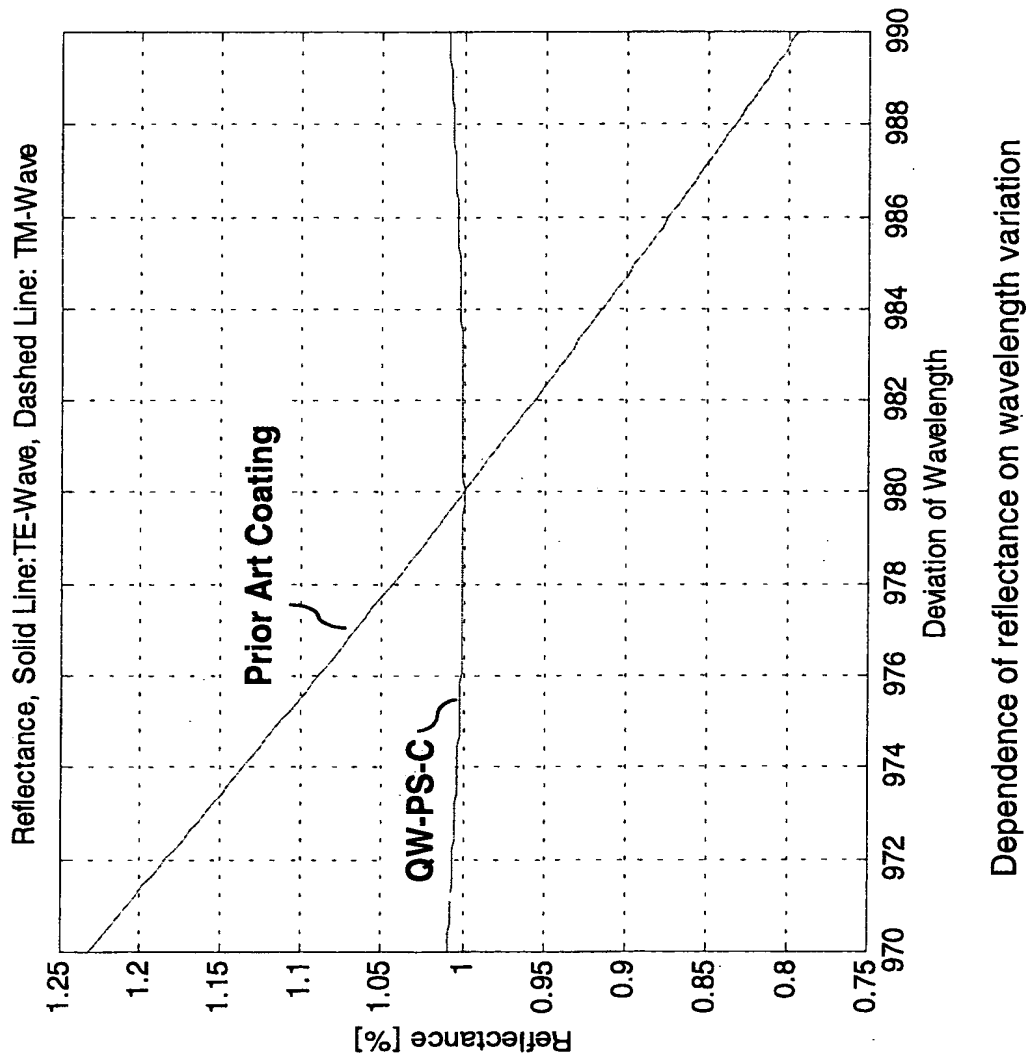


Fig. 11**Process parameters**

Coating	2%SiH <sub>4</sub> /He	N <sub>2</sub>	NH <sub>3</sub>	Plasma Power	Substrate Temp	Pressure
Prior art	300 sccm	330 sccm	Variable (~11.5sccm)	20 Watts	300 °C	1.4 Torr
QW-PS-C	403 sccm	35 sccm	Variable (~12.2sccm)	25 Watts	300 °C	1.4 Torr